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SNS College of Technology, Coimbatore-35.
(Autonomous)
B.E/B.Tech- Internal Assessment -I
Academic Year 2022-2023(Odd)
Fifth Semester
Electronics and Communication Engineering
19ECB302 – VLSI Design

B

Time: 1^{1/2} Hours**Maximum Marks: 50****Answer All Questions**

PART - A (5 x 2 = 10 Marks)				CO	Blooms
1	List the steps involved in manufacturing of CMOS IC fabrication.			CO1	REM
2	What are the two types of CMOS layout design rules?			CO1	UND
3	Differentiate between Threshold Voltage and Body Effect.			CO1	ANA
4	Define Drain punch through condition in CMOS circuits.			CO2	REM
5	Recall the advantages of Transmission Gate logic			CO2	REM
PART – B (2*13 = 26 Marks)					
				CO	Blooms
6.	(a)	Describe mask levels for the CMOS Fabrication P-well process with necessary diagrams.	14	CO1	UND
		(or)			
	(b)	Build the MOS C-V Characteristics with its neat diagrams and explanation.	14	CO1	APP
7	(a)	Analyze pass transistor and Transmission gates with neat sketches.	14	CO2	ANA
		(or)			
	(b)	Develop any two examples of combinational logic with its circuit diagrams	14	CO2	APP
PART – C (1*14 = 14 Marks)				CO	Blooms
8	(a)	Survey the concept of Twin Tub process Logic with relevant diagrams	14	CO1	ANA
		(or)			
	(b)	Apply the different mask levels for drawing stick diagram of CMOS NAND gate and a.b +c with its circuit diagram.	14	CO1	APP

CO-Course Outcomes, **REM**-Remembering, **UND**-Understanding, **APP**-Applying, **ANA**-Analyzing

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